

# SUBSTRATE PROCESSING APPARATUS, PROTECTOR, METHOD OF MANUFACTURING SEMICONDUCTOR DEVICE, AND PROGRAM

## ABSTRACT

There is provided a technique that includes: a process container configured to process a substrate; a gas supplier configured to be capable of supplying a gas that processes the substrate into the process container; a protector arranged along an inner peripheral surface of the process container, a height of the protector being adjustable by rotation in a circumferential direction; and a controller configured to be capable of performing a control to process the substrate by supplying the gas after the height of the protector is adjusted.

Fig. 1